CONTENTS

Despotuli A. L., Andreeva A. V. *Prospects of Deep-Sub-Voltage Nanoelectronics and Related Technologies in Russia* 2 The tendencies in nanoelectronics development are considered in a long term perspective. The conclusion made is that within the period after 2015 the deep-sub-voltage nanoelectronics (DSVN), i. e. integrated circuits (ICs) of ~ 10^{11} — 10^{12} cm⁻² component density operating near the theoretical limit of energy consumption per 1 bit processing, will find wide application. The outstripping development of DSVN in Russia as a prospective national task and as an indispensable condition for a successful participation of the country in the global technological race is substantiated. The challenges of micron sized high-capacity capacitors for DSVN and technologies connected with DSVN are analyzed. It is shown that applications involving autonomous nano- and microsystems require storage devices with capacity density $\delta_C > 50 \ \mu F/cm^2$ which cannot be achieved with traditional design capacitors. Theoretical estimates and experimental data on innovation impulse micron-sized supercapacitors on the base of advanced superionic conductors (nanoionic supercapacitors) with $\delta_C > 100 \ \mu F/cm^2$ are presented. It is also shown that the lower time limit of nanoionic supercapacitors recharging would be ~ 10^{-7} s if the problem of thermal overheating of ICs with a component density of ~ $10^{12} \ cm^{-2}$ will not be solved. The potential world market of high-capacity sub-voltage storage devices is estimated.

Keywords: deep-sub-voltage nanoelectronics, nanoionic supercapacitors.

Keywords: bamboo-shaped nanotubes, growth of bamboo-shaped nanotubes, electrostatic and electron emission of bamboo-shaped nanotubes.

Keywords: nanostructures, temperature fields, elementary balances metod, mathematical models, thermal processes.

Keywords: compound semiconductors, super-high speed pin-photodiode, technological computer-aided design.

Possible technology ways to produce capacitor elements of ferroelectric random access memory (FeRAM) are consider: chemical solution deposition, physical vapour deposition, chemical vapour deposition, atomic layer deposition. Technology and material prospects of FeRAM are discussed.

Keywords: active dielectrics, ferroelectrics random access memory, lead zirconate titanate, chemical solution deposition, misted source chemical solution deposition, physical vapour deposition, chemical vapour deposition, atomic layer deposition, nanostructeres.

Belozubov E. M., Belozubova N. E. Thin-Film Capacitive MEMS Structures for Measurement of Electrode Temperature. .42 Design and producibility problems as concerns thin-film capacitive MEMS structures, which are capable to measure electrode temperature, are submitted. Practical realization of such MEMS structures in thin-film capacitive pressure transducers is presented. Such implementation makes it possible to reduce the dependence of steady-state and transient temperatures. Keywords: thin-film capacitive MEMS structures, temperature, vibration, lead, electrode temperature measurement.

Vopilkin E. A., Shashkin V. I., Drozdov Yu. N., Daniltsev V. M., Gusev S. A., Shuleshova I. Yu. A Bymorph GaAs Microbeam A design of a GaAs bymorph microbeam MEMS piezoelectric actuator is proposed. The calculation of the dependence of the beam deflection on the applied bias is carried out. A piezoelectric actuator consisting of a 2 µm thick microbeam with dimensions $100 \times 15 \,\mu\text{m}$ is fabricated. The measured by the interferometer dependence of the beam deflection on the applied bias is in good agreement with the calculated one.

Keywords: bimorph, piezoelectric actuator, microbeam.

Obraztsov R. M. Small-Sized Vibrating Gyroscope with Beam-Type Bimorph Sensitive Element Made from Piezoelectric Developing, production and tuning features of small-sized vibrating gyroscope with beam-type bimorph sensitive element made from piezoelectric ceramics have researched.

Keywords: gyroscope, piezoelectric ceramics, bimorph.

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